



**Clean n' Mild  
Facial Cleanser  
(CPF 4600)**

# Clean n' Mild Facial Cleanser (CPF 4600)

Clean n' Mild is a water based and cold processed skin cleanser, formulated with balanced pH and mild ingredients. It is a face wash that gently cleanses the skin. It leaves the skin smooth and silky, gently removing makeup and impurities.

Trade name	Supplier	INCI name	Wt.%
Water		Water	81.30
EcoSense™ GL-60 HA Surfactant	DOW	Glycolipids	2.5
EcoSense™ GL-60 HL Surfactant	DOW	Glycolipids	2.5
EcoSense™ APP-1000 Surfactant	DOW	Caprylyl/Capryl Glycosides/Xylosides	3.0
Butylene Glycol		Butylene Glycol	5.0
Glycerin		Glycerin	5.0
Euxyl PE 9010 / Ashland	Ashland	Phenoxyethanol (and) Ethylhexylglycerin	0.5
Lavender	Bramble Berry	Lavandula Angustifolia (Lavender) Essential Oil	0.2
Triethanolamine		Triethanolamine	q.s.
Citric Acid		Citric Acid	q.s.

## Procedure:

1. Mix ingredients together step-wise.
2. Add Triethanolamine to neutralize, pH ~7. This will help solubilize Lavender Oil.
3. Add Citric Acid to pH 5.5.



Images: dow\_58822723457, dow\_78605853555

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Form No. 27-3499-01-0223 S2D